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(54) Title: BLOCK COPOLYMER-ASSISTED NANOLITHOGRAPHY

(57) Abstract: In accordance with an embodiment of the disclosure, a method for forming sub- micron size nanostructures on a substrate surface includes contacting a substrate with a tip coated with an ink comprising a block copolymer matrix and a nanostructure precursor to form a printed feature comprising the block copolymer matrix and the nanostructure precursor on the substrate, and reducing the nanostructure precursor of the printed feature to form a nanostructure having a diameter (or line width) of less than 1μm.